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A study of the interface kinetics affecting cylindrical phase separation in PS-b-PMMA copolymer thin films

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In this study a controlled examination was undertaken in order to confirm and compare the parameters affecting PS-b-PMMA copolymer thin film nano-masks. A PS-b-PMMA copolymer with a molecular weight of 67 100 g.mol-1 (70:30) was used to produce thin film nano-masks on treated and untreated Si substrates. By simultaneously annealing samples of differing thin film thicknesses on the two types of treated silicon substrate in the same ambient (vacuum of 6 \times 010 \times 0° (-2) mbar) a direct comparison is made between the samples. It is shown that the average domain spacing's for perpendicular-to substrate morphology is approximately 40 nm. Additionally, the effect of thin film thickness on the formation of a perpendicular morphology is clearly demonstrated, with a thickness repeat period of approximately 32 nm. Importantly, interface effects are seen between the thin film and both the substrate and vacuum interfaces, and a minimum vacuum quality is shown to be a necessary requirement for producing uniform perpendicular morphologies across the thin film.

Are you currently a postgraduate student? (Yes/No)

Yes

At what level of studies are you currently? (Hons/MSc/PhD)

PhD

Please provide the name and email address of your supervisor.

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